


**Form 1449 (Modified)**
**Information Disclosure  
Statement By Applicant**

(Use Several Sheets if Necessary)

Atty Docket No.

LAM1P157/P0718

Application No.:

09/746,900

Applicant:

ANNAPRAGADA et al.

Filing Date

12/22/00

Group

2812

**U.S. Patent Documents**

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A						
	B						
	C						
	D						
	E						
	F						
	G						
	H						
	I						

**Foreign Patent or Published Foreign Patent Application**

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	J							
	K							
	L							
	M							
	N							

**Other Documents**

TC 1700

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
<i>AMC</i>	O	U.S. Patent Application No. 09/746,901, Entitled "Method of Preventing Damage to Organo-Silicate Glass Materials during Resist Stripping", Filed 12/22/00, Inventor(s): Annapragada
<i>AMC</i>	P	U.S. Patent Application No. 09/746,894, Entitled "Combined Resist Strip and Barrier Etch Process for Dual Damascene Structures", Filed 12/22/00, Inventor(s): Annapragada et al.
	Q	

*R. Michelle Howell*

Date Considered

10-07-02

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Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Pg. 1 of 1

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